ISO 14706:2000-12 (E)

Surface chemical analysis - Determination of surface elemental contamination on silicon wafers by total-reflectio n X-ray fluorescence (TXRF) spectroscopy

Contents

Page

Foreword iv

Introduction v

1 Scope 1

2 Normative reference 1

3 Terms and definitions 1

4 Abbreviated terms 2

5 Principle 2

6 Apparatus 2

7 Environment for specimen preparation and measurement 3

8 Calibration reference materials 3

9 Safety 3

10 Measurement procedure 4

11 Expression of results 5

12 Precision 6

13 Test report 6

Annex A (informative) Reference materials 7

Annex B (informative) Relative sensitivity factor 8

Annex C (informative) Preparation of reference materials [6] 11

Annex D (informative) VPD-TXRF method 14

Annex E (informative) Glancing-angle settings 16

Annex F (informative) International inter-laboratory test results 20

Bibliography 23